

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Cyril Cabral, Jr., et al. **Examiner:** Long Pham
Serial No: 10/662,900 **Art Unit:** 2814
Filed: September 15, 2003 **Docket:** YOR920030218US1 (16714)
For: REDUCTION OF SILICIDE
FORMATION TEMPERATURE ON
SiGe CONTAINING SUBSTRATES
Dated: November 28, 2007

Confirmation No: 1278

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

RESPONSE TO EX PARTE OUALYE OFFICE ACTION

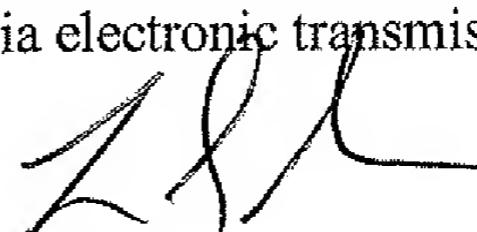
Sir:

In response to the Office Action dated September 28, 2007, applicants submit the following amendments and remarks for entry into the record of the above-identified patent application.

CERTIFICATION OF ELECTRONIC TRANSMISSION

I hereby certify that this document is being filed in the United States Patent and Trademark Office on the date shown below via electronic transmission.

Dated: November 28, 2007



Leslie S. Szivos, Ph.D.